

WHAT IS CLAIMED IS:

1. A substrate assembly for a display comprising:
a substrate; and
a film provided over said substrate and comprising aluminum nitride and oxygen.
2. A substrate assembly for a display comprising:
a substrate; and
an Al₂O₃ film provided over said substrate.
3. A substrate assembly for a display comprising:
a substrate; and
an AlN film containing oxygen provided over said substrate.
4. A substrate assembly for a display comprising:
a substrate; and
a film provided over said substrate and comprising aluminum nitride and oxygen,
wherein said oxygen is contained in said film at 0.001 to 10 atomic percent.
5. A substrate assembly according to claim 1 wherein said substrate comprises glass.
6. A substrate assembly according to claim 2 wherein said substrate comprises glass.
7. A substrate assembly according to claim 3 wherein said substrate comprises glass.
8. A substrate assembly according to claim 4 wherein said substrate comprises glass.
9. A substrate assembly according to claim 1 wherein said film comprising the
aluminum nitride and the oxygen has a thermal conductivity of 200 Wm⁻¹K⁻¹ or more.
10. A substrate assembly according to claim 2 wherein said Al₂O₃ film has a thermal
conductivity of 200 Wm⁻¹K⁻¹ or more.
11. A substrate assembly according to claim 3 wherein said AlN film has a thermal
conductivity of 200 Wm⁻¹K⁻¹ or more.

12. A substrate assembly according to claim 4 wherein said film comprising the aluminum nitride and the oxygen has a thermal conductivity of $200 \text{ Wm}^{-1}\text{K}^{-1}$ or more.

13. A substrate assembly according to claim 1 wherein said film comprising the aluminum nitride and the oxygen has a thickness of 500 Å to 3 µm.

14. A substrate assembly according to claim 2 wherein said AlNO film has a thickness of 500Å to 3 μm.

15. A substrate assembly according to claim 3 wherein said AlN film has a thickness of 500Å to 3 µm.

16. A substrate assembly according to claim 4 wherein said film comprising the aluminum nitride and the oxygen has a thickness of 500Å to 3 µm.

17. A substrate assembly according to claim 1 wherein said film comprising the aluminum nitride and the oxygen is an insulating film.

18. A substrate assembly according to claim 2 wherein said Al_xNO film is an insulating film.

19. A substrate assembly according to claim 3 wherein said AlN film is an insulating film.

20. A substrate assembly according to claim 4 wherein said film comprising the aluminum nitride and the oxygen is an insulating film.